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INFORMATION DISCLOSURE CITATION IN AN APPLICATION				DOCKET NUMBER SLA 0468	R AP	PLICATIO	N NUMBE	
				APPLICANT Apostolos Voutsas, Yukihiko Nakata and Takeshu Hosoda				
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Ka.	Article entitled, "Influence of ¹⁶ O, ¹² C, ¹⁴ N, and Noble Gases on the Crystallization of Amorphous Si Layers", published in J. Appl. Phys., Vol. 48, by E. F. Kennedy et al., (1977), pp. 4241-4246							
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